

# Papers by Bell Laboratories Authors

## CHEMISTRY

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**Investigation of the Ti-Pt Diffusion Barrier for Gold Beam Lead on Aluminum.** S. P. Murarka, H. J. Levinstein, I. Blech, T. T. Sheng, and M. H. Read, *J. Electrochem. Soc.*, **125** (January 1978), pp. 156-162.

**Plasma-Grown Oxide on GaAs—Semiquantitative Chemical Depth Profiles Obtained Using Auger Spectroscopy and Neutron Activation Analysis.** C. C. Chang, R. P. H. Chang, and S. P. Murarka, *J. Electrochem. Soc.*, **125** (March 1978), pp. 481-487.

**Raman Study of the  $O_2F_2 + VF_5$  Reaction: Isolation and Identification of an Unstable Reaction Intermediate.** J. E. Griffiths, A. J. Edwards, W. A. Sunder, and W. E. Falconer, *J. Fluorine Chem.*, **11** (1978), pp. 119-142.

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**Effect of Interfacial Reactions on the Electrical Characteristics of Metal Semiconductor Contacts.** E. H. Nicollian and A. K. Sinha, *Electrochem. Soc. Monograph Thin Films—Interdiffusion and Reactions*, New York: John Wiley & Sons (May 1978), pp. 481-531.

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**Interatomic Internal Photoemission Peaks in (Auger) Electron Spectra.** C. C. Chang, *J. Electron. Spectros. Relat. Phenom.*, **13** (1978), pp. 255-261.

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## MATERIALS SCIENCE AND ENGINEERING

**Preparation and Electropolishing of Thin Gold Disc Specimens for Transmission-Electron-Microscope Examination.** W. F. Peck, Jr. and S. Nakahara, *Metallography*, 11 (1978), pp. 347-354.

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